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			_U. S	S. Patent Do	cuments		,		
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	AA							<u> </u>	
7~	AB	5,470,800	11-28-95	Muroyar	na	437	238	03-26-	-93
	AC	6,037,275	03-14-00	Wu, et a	l.	438	780	08-27-	-98
	AD	6,270,572	08-07-01	Kim, et a	ıL	117	93	08-09-	.99
	AE	2002/0001974	01-03-02	Chan		438	785	06-20-	-01
N	AF	6,391,803	05-21-02	Kim, et a	ıL	438	787	06-20-	-01
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7	AL	06132276	05-13-94	Japan		H01L	21/312		х
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	AP	2001002990	01-09-01	Japan		C09D	183/04		X
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		OTHER	DOCUM	ENTS (Includi	ng Autho	r, Title, I	Date, Pertine	nt Pages,	Etc.)
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ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

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Title of Invention

Method of Forming Silicon Dioxide Using Siloxane

Application Number:

10/782094

Confirmation Number:

4756

First Named Applicant:

Jae-Eun Park

Attorney Docket Number:

SAM-0483

Art Unit:

Examiner:

Search string:

(6664156 or 5037514 or 6534395 or 20020164890 or 20030015764 or

20020047151).pn

US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
W	1	6664156	2003-12-16	Ang, et al.			
TN	2	5037514	1991-08-06	Yamazaki			
TM	3	6534395	2003-03-18	Werkhoven, et al.			

US Published Applications

Note: Applicant is not required to submit a paper copy of cited US Published Applications

init	Cite.No.	Pub. No.	Date	Applicant	Kind	Class	Subclass
TN	1	20020164890	2002-11-17	Kwan, et al.			
TN	2	20030015764	2003-01-23	Raaijmakers, et al.			
\mathcal{T}	3	20020047151	2002-04-25	Kim, et al.			

Remarks

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ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

Title of Invention

Method for forming silicon dioxide film using siloxane

Application Number:

10/782094

Confirmation Number:

4756

First Named Applicant:

Jae-Eun Park

Attorney Docket Number:

SAM-0483

Art Unit:

Examiner:

Search string:

(20040096582).pn

US Published Applications

Note: Applicant is not required to submit a paper copy of cited US Published Applications

init	Cite.No.	Pub. No.	Date	Applicant	Kind	Class	Subclass
M	1	20040096582	2004-05-20	Wang, et al.			

Remarks

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MAR 1 4 2005 Docket Number (Optional) Application Number Subst. Form PTO-1449 10/782,094 INFORMATION DISCLOSURE CITATION SAM-0483 Applicant IN AN APPLICATION Jae-eun Park, et al. Filing Date Group Art Unit (Use several sheets if necessary) 02/19/04 2813 U. S. Patent Documents FILING DATE IF APPROPRIATE EXAMINER INITIALS DOCUMENT NUMBER DATE NAME CLASS SUBCLASS BA BBBC BD BE \mathbf{BF} BG BH BI BJ BKFOREIGN PATENT DOCUMENTS Translation DOCUMENT NUMBER DATE COUNTRY CLASS SUBCLASS BL BM X H01L 21/316 TN 02-2579 01/10/02 Korea BN H01L 21/20 X 02-44422 06/15/02 Korea BO BP BO OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.) BR BS BT

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ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

Title of Invention

Method for forming silicon dioxide film using siloxane

Application Number:

10/782094

Confirmation Number:

4756

First Named Applicant:

Jae-eun Park

Attorney Docket Number:

SAM-0483

Art Unit:

Examiner:

Search string:

(3313792).pn

US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
m	1	3313792	1967-04-11	Duck, et al.			

Remarks

Note: Remarks are not for responding to an office action.

Part 1 of 1.

Signature

Examiner Name	Date
T. NRWEN	12/16/05